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Form 1449*

Sheet 1 of 1

**INFORMATION DISCLOSURE STATEMENT
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Applicant: Leonard Forbes et al.

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**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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gk	0291951	11/23/1988	European	H01L	29/64		
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*Substitute Disclosure Statement Form (PTO-1449)

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